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	Application No.	Applicant(s)	
	10/796,893	CHAN ET AL.	
Notice of Allowability	Examiner	Art Unit	
	Steven H. Rao	2814	
The MAILING DATE of this communication appearance All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap or other appropriate communication IGHTS. This application is subject t	plication. If not included n will be mailed in due course.	
1. This communication is responsive to <u>3/23/2006</u> .			
2. ☑ The allowed claim(s) is/are <u>25-28</u> .			
<ul> <li>3. ☐ Acknowledgment is made of a claim for foreign priority unallocation.</li> <li>a) ☐ All b) ☐ Some* c) ☐ None of the:</li> <li>1. ☐ Certified copies of the priority documents have</li> </ul>			
<ol><li>Certified copies of the priority documents have</li></ol>	been received in Application No	·	
<ol><li>Copies of the certified copies of the priority do</li></ol>	cuments have been received in this	national stage application from	the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the requiremen	its
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give			)F
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.		
(a) ☐ including changes required by the Notice of Draftspers		-948) attached	
1)  hereto or 2)  to Paper No./Mail Date			
(b) including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in the 0	Office action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the			
6. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT			
Attachment(s)	e Marie de la companya dela companya dela companya dela companya de la companya dela companya de la companya dela companya dela companya de la companya de la companya de la companya de la companya dela companya de la companya dela co	D ( (A () ) (DTO (FD)	
1. Notice of References Cited (PTO-892)		Patent Application (PTO-152)	
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. 🗍 Interview Summary Paper No./Mail Da		
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date	Paper No./Mail Da 98), 7. ☐ Examiner's Amend	ment/Comment	
4.   Examiner's Comment Regarding Requirement for Deposit	8. X Examiner's Statem	ent of Reasons for Allowance	
of Biological Material	9.  Other		

## Response to Amendment

Applicants' amendment filed on arch 17, 2006 has been entered and forwarded to the Examiner on March 23, 2006.

Therefore claims 25 to 28 as amended by the amendment of March 14, 2006 are currently pending in the Application.

Claims 1-24 were previously cancelled.

## Allowable Subject Matter

Claims 25-28 are allowed.

The following is an examiner's statement of reasons for allowance:

The prior art taken either singularly or in combination fails to anticipate or fairly suggest the limitation of the dependent claims, in such manner that a rejection under 35 U.S.C. 102 or 103 would be proper. The applied prior art fails to teach a combination of all the claimed features as presented in independent claims, which include a semiconductor device as claimed in independent claim 25 including a multilevel interconnect structure having a semiconductor surface having metal electrical contacts having there over an inter metal dielectric layer of low-K compound, wherein the inter metal dielectric layer of low-K compound includes a first dielectric layer comprising a first network of air filled trenches, and a second dielectric layer deposited on the first dielectric layer and in contact therewith wherein the second dielectric layer comprises of a second network of trenches filled with air, the second network of trenches further is in contact with and intersects with the first network of trenches and forms an interconnected network of trenches one above the other filled with air and a layer of

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oxide over the second dielectric layer, wherein the oxide layer includes a first oxide layer having openings there-through which (openings) are aligned with the intersections between the first and second network of trenches and a second oxide layer closing the openings in the first oxide layer. (see also USP Nos. 6,228,770 and parent- 6,730,571).

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Steven H. Rao whose telephone number is (571)272-1718. The examiner can normally be reached on 8.00 to 5.00.

The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Steven H. Rao

Patent Examiner

May 25,2 006.

PRIMARY EXAM.